

Title (en)  
IMPEDANCE-ASSISTED ELECTROCHEMICAL TECHNIQUE AND ELECTROCHEMISTRY FOR REMOVING MATERIAL, PARTICULARLY EXCESS EMITTER MATERIAL IN ELECTRON-EMITTING DEVICE

Title (de)  
IMPEDANZUNTERSTÜTZTES ELEKTROCHEMISCHES VERFAHREN UND ELEKTROCHEMIE ZUM ENTFERNEN VON MATERIAL, INSBESONDERE VON ÜBERFLÜSSIGEM EMITTERENDEM MATERIAL, IN EINER ELEKTRONENEMITTIERENDEN VORRICHTUNG

Title (fr)  
TECHNIQUE ELECTROCHIMIQUE ASSISTEE PAR IMPEDANCE ET PROCEDE ELECTROCHIMIQUE PERMETTANT D'ELIMINER UN MATERIAU, NOTAMMENT UN MATERIAU GENERATEUR D'EXCEDENTS, DANS UN DISPOSITIF EMETTEUR D'ELECTRONS

Publication  
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Application  
**EP 98931401 A 19980629**

Priority  

- US 9812801 W 19980629
- US 88470097 A 19970630
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Abstract (en)  
[origin: WO9900537A1] An impedance-assisted electrochemical procedure is employed for selectively removing certain material from a structure without significantly electrochemically attacking, and thus without significantly removing, certain other material of the same chemical type as the removed material.

IPC 1-7  
**C25D 5/02**; **C25D 5/48**; **B23H 3/00**; **H01J 1/02**; **H01J 1/62**; **B44C 1/22**; **H01J 9/02**; **C25F 3/00**; **C25F 5/00**

IPC 8 full level  
**C25F 3/02** (2006.01); **C25F 3/14** (2006.01); **C25F 5/00** (2006.01); **H01J 9/02** (2006.01)

CPC (source: EP KR)  
**C25F 3/00** (2013.01 - KR); **H01J 9/025** (2013.01 - EP)

Citation (search report)  

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- [A] WO 9709730 A2 19970313 - FED CORP [US]
- [A] WO 9507543 A1 19950316 - SILICON VIDEO CORP [US]
- [A] DATABASE WPI Section Ch Week 199116, Derwent World Patents Index; Class E14, AN 1991-112827, XP002144729
- [PX] CHEMICAL ABSTRACTS, vol. 129, no. 6, 10 August 1998, Columbus, Ohio, US; abstract no. 73363, KOBAYASHI, NOBUO ET AL: "Electrolytic bath and method for electrolytic peeling" XP002144728 & JP H10140400 A 19980526 - EBARA UDYLITE KK
- See references of WO 9900537A1

Designated contracting state (EPC)  
DE FR GB IE

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